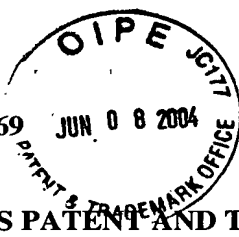


Practitioner's Docket No. 081468-0306369  
Client Reference: P-1790.000-US



**PATENT**

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

In re application of: OTTENS et al.

Application No.: 10/743,272

Confirmation No.: 4455

Filed: December 23, 2003

Group No.: 1756

Examiner: TBA

For: OPTIMIZED CORRECTION OF WAFER THERMAL DEFORMATIONS IN A LITHOGRAPHIC PROCESS

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

**SUPPLEMENTAL APPLICATION DATA SHEET**  
**37 C.F.R. § 1.76(c)**

The following information on the Application Data Sheet is changed as indicated:

**BIBLIOGRAPHIC DATA**

**1. Applicant information is being added.**

Fifth Applicant: Willem Jurrianus VENEMA

Citizenship: The Netherlands

Residence: Brabis 21, NL-5641 JT Eindhoven, The Netherlands

Sixth applicant: Boris MENCHTCHIKOV

Citizenship: Russia

Residence: Pieter Borpad 16, NL-5624 EP Eindhoven, The Netherlands

Date: June 8, 2004

E. Rico Hernandez  
Registration No. 47641  
PILLSBURY WINTHROP LLP  
P.O. Box 10500  
McLean, VA 22102  
(703) 905-2088  
Customer No. 00909